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### AMPLIFIER CIRCUIT

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#### Abstract

A first embodiment is directed to a circuit including a positive biasing circuit with a drive PMOS for biasing in subthreshold, a negative biasing circuit with a drive NMOS for biasing in subthreshold, and an amplification circuit coupled to the biasing circuits. The amplification circuit includes a first stage with a first boosting stage, a second stage with a second boosting stage, and a resistive element coupled between the first and second stages. A second embodiment is directed to a folded cascode operational amplifier wherein a value of the resistive element is selected to place at least one of a drive MOS in subthreshold. A third embodiment is directed to an integrated circuit with a resistive area neighboring a first boosting area and a second boosting area, the resistive area including a resistive element directly connected to a drive PMOS and a drive NMOS.

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## Background/Summary

**CROSS-REFERENCE TO RELATED APPLICATIONS** [0001] This application is a continuation of and claims the benefit of priority to U.S. application Ser. No. 18/442,176, filed Feb. 15, 2024 (now allowed), which claims the benefit of priority to U.S. application Ser. No. 18/302,016, filed Apr. 18, 2023 (now U.S. Pat. No. 11,949,391), which claims the benefit of priority to U.S. application Ser. No. 17/658,822 filed Apr. 11, 2022 (now U.S. Pat. No. 11,658,627), which claims the benefit of priority to U.S. application Ser. No. 17/355,491, filed Jun. 23, 2021 (now U.S. Pat. No. 11,336,246), which claims the benefit of priority under 35 U.S.C. 119 (e) to U.S. provisional application No. 63/166,084, filed Mar. 25, 2021. The disclosures of the above-referenced applications are expressly incorporated herein by reference in their entireties.

### TECHNICAL FIELD

[0002] The disclosure relates to an amplifier circuit and an integrated circuit implementing the amplifier circuit.

### BACKGROUND

[0003] Operational amplifiers are high-gain electronic voltage amplifying circuits with a differential input and one or more outputs. The operational amplifiers produce an output potential that is typically thousands of times larger than a potential difference between its input terminals. Operational amplifiers may be used in different amplification modes including, but not limited to, linear amplification, non-linear amplification, and/or frequency-dependent amplification. Further, operational amplifiers are used in both analog and digital circuits as a building block for multiple applications. And, because operational amplifiers can be adjusted with external components for specific operations, operational amplifiers are highly adaptable for customized operations. For example, the gain, input, output, impedance, and bandwidth of an operational amplifier can be customized with external components.

[0004] Operational amplifiers may be implemented in integrated circuits with specific configurations of active and/or passive electronic devices. For example, operational amplifiers may be fabricated within integrated circuits using networks of transistors configured for high-gain transduction. Such operational amplifiers may be used for on-chip amplification of weak signals, noise reduction, and other signal processing operations. For example, operational amplifiers in integrated circuits can be used to filter and amplify signals inputted in processing and/or logic circuits within the integrated circuit. Operational amplifiers in integrated circuits may use BJT and/or CMOS technology, and may employ cascading configurations to adjust gains, operative frequency, and signal phasing.

[0005] The disclosed systems, apparatus, and methods for operational amplifiers and integrated circuits are directed to addressing one or more problems or challenges in the prior art.

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## Description

### BRIEF DESCRIPTION OF THE DRAWINGS

[0006] Aspects of the present disclosure are best understood from the following detailed description when read with the accompanying figures. It is noted that, in accordance with the standard practice in the industry, various features are not drawn to scale. In fact, the dimensions of the various features may be arbitrarily increased or reduced for clarity of discussion.

[0007] FIG. 1 shows a circuit diagram of a duty cycle corrector (DCC) with synchronous input clock in accordance with some embodiments of the present disclosure.

[0008] FIG. 2 shows a circuit diagram of an exemplary operational amplifier in accordance with some embodiments of the present disclosure.

[0009] FIG. 3A shows a circuit diagram of an exemplary configuration of drive transistors using a resistor in accordance with some embodiments of the present disclosure.

[0010] FIG. 3B shows a circuit diagram of an exemplary configuration of drive transistors using a transistor in accordance with some embodiments of the present disclosure.

[0011] FIG. 3C shows a circuit diagram of an exemplary configuration of drive transistors using a diode in accordance with some embodiments of the present disclosure.

[0012] FIG. 4A shows a circuit diagram of an exemplary configuration of an operational amplifier using variable resistors in accordance with some embodiments of the present disclosure.

[0013] FIG. 4B shows a circuit diagram of an exemplary configuration of operational amplifier using triode transistors in accordance with some embodiments of the present disclosure.

[0014] FIG. 5A shows a circuit diagram of a first exemplary boosting stage in accordance with some embodiments of the present disclosure.

[0015] FIG. 5B shows a circuit diagram of a second exemplary boosting stage in accordance with some embodiments of the present disclosure.

[0016] FIG. 6A shows a circuit diagram of an exemplary boosting stage using a resistive load in accordance with some embodiments of the present disclosure.

[0017] FIG. 6B shows a circuit diagram of an exemplary boosting stage using an inductive load in accordance with some embodiments of the present disclosure.

[0018] FIG. 6C shows a circuit diagram of an exemplary boosting stage using an active load in accordance with some embodiments of the present disclosure.

[0019] FIG. 6D shows a circuit diagram of an exemplary boosting stage using an active PMOS diode load in accordance with some embodiments of the present disclosure.

[0020] FIG. 6E shows a circuit diagram of an exemplary boosting stage using an active NMOS diode load in accordance with some embodiments of the present disclosure.

[0021] FIG. 7 shows a circuit diagram of a first exemplary amplifier with active loads and resistive coupling for subthreshold biasing in accordance with some embodiments of the present disclosure.

[0022] FIG. 8 shows a circuit diagram of a second exemplary amplifier with subthreshold biasing using a coupling resistor in accordance with some embodiments of the present disclosure.

[0023] FIG. 9A shows an exemplary schematic of a first layout floor plan for an integrated circuit in accordance with some embodiments of the present disclosure.

[0024] FIG. 9B shows an exemplary schematic of a second layout floor plan for an integrated circuit in accordance with some embodiments of the present disclosure.

[0025] FIG. 10 shows a flow chart of an exemplary method of operation of an amplifier circuit in accordance with some embodiments of the present disclosure.

### DETAILED DESCRIPTION

[0026] The following disclosure provides many different embodiments, or examples, for implementing different features of the provided subject matter. Specific examples of components and arrangements are described below to simplify the present disclosure. These are, of course,

merely examples and are not intended to be limiting. For example, the formation of a first feature over or on a second feature in the description that follows may include embodiments in which the first and second features are formed in direct contact, and may also include embodiments in which additional features may be formed between the first and second features, such that the first and second features may not be in direct contact. In addition, the present disclosure may repeat reference numerals and/or letters in the various examples. This repetition is for the purpose of simplicity and clarity and does not in itself dictate a relationship between the various embodiments and/or configurations discussed.

[0027] Further, spatially relative terms, such as “beneath,” “below,” “lower,” “above,” “upper” and the like, may be used herein for ease of description to describe one element or feature's relationship to another element(s) or feature(s) as illustrated in the figures. The spatially relative terms are intended to encompass different orientations of the device in use or operation in addition to the orientation depicted in the figures. The apparatus may be otherwise oriented (rotated 90 degrees or at other orientations) and the spatially relative descriptors used herein may likewise be interpreted accordingly.

[0028] Further, connectivity terms such as “connected,” “coupled,” “joined,” “attached,” and the like, may be used herein for ease of description to describe elements that have an electrical, electromagnetic, radio frequency, or ultrasonic connectivity. Moreover, connectivity terms may denote general electrical or magnetic communication between components. These connectivity terms may denote a direct connection (i.e., two components being connected without any intervening element) or an indirect connection (i.e., two components being connected through one or more intervening elements).

[0029] FIG. 1 shows a circuit diagram of a duty cycle corrector (DCC) **100** with synchronous input clock in accordance with some embodiments of the present disclosure. In some embodiments, DCC **100** may be configured to adjust a clock duty cycle to a selected percentage. For example, DCC **100** may be configured to adjust the clock duty cycle to modify clock signals for a double data rate (DDR), a half-rate clock data recovery (CDR), and/or a delay locked loop (DLL). In some embodiments, DCC **100** may be used in applications using multi-phase clocks, MUX/DEMUX circuits, or other circuits with fixed rising edge requirements. DCC **100** may be used for analog, semi-digital, and/or digital applications.

[0030] DCC **100** includes a clock input CLK\_IN **114** which can be connected to an external input circuit transmitting an input signal to be modified and/or corrected. DCC **100** also includes differential inputs of a signal CKP **102** and a signal CKN **104**. In some embodiments, as shown in FIG. 1, signal CKP **102** and signal CKN **104** are generated by operational amplifiers in DCC **100**. In such embodiments, as further discussed below, CKP **102** is generated by an inverter **126** and CKN **104** is generated by an inverter **128**. And CKP **102** and CKN **104** can be used as feedback signals. Thus, as shown in FIG. 1, inputs CKP **102** and CKN **104** are connected to an amplifier **200** which is connected to a power node PWD\_DCC **106**. Amplifier **200** is further discussed in connection with FIG. 2.

[0031] As shown in FIG. 1, an output of amplifier **200** is coupled to a first control stage **108**. The first control stage **108** includes first coupled CMOS transistors **108A**, second coupled CMOS transistors **108C**, and a first connection node **108B**. First coupled CMOS transistors **108A** are connected to the amplifier **200** output, first connection node **108B** is connected to a first reset control signal RSTB1 **110**, and second coupled transistors **108C** are connected to a first tie control signal tie0 **112**. As shown in FIG. 1, while the output of amplifier **200** and an input of signal tie0 **112** are connected to drain/source of First coupled CMOS transistors **108A** and second coupled CMOS transistors **108C**, signal RSTB1 **110** is coupled to first connection node **108B**. Further, first coupled CMOS transistors **108A**, second coupled CMOS transistors **108C** may be coupled together through their respective gates.

[0032] DCC **100** includes a second control stage **122** with a configuration similar to the one

described above for first control stage **108**. In some embodiments, as shown in FIG. **1**, the second control stage **122** includes third coupled CMOS transistors **122A**, fourth coupled CMOS transistors **122C**, and a second connection node **122B**. Third coupled CMOS transistors **122A** are coupled with a control node **116**. Although not shown, control node **116** may be coupled to an output of another amplifier, similar to amplifier **200**. In other embodiments, however, control node **116** may be connected to another circuit and/or electronic device. Second connection node **122B** is coupled to a second reset control signal RSTB2 **118** and fourth coupled CMOS transistors **122C** are coupled to receive a second tie control signal tie1 **120**. Similar to the connections in the first control stage **108**, the control node **116** and an input for signal tie1 **120** are connected to drain source nodes of third coupled CMOS transistors **122A**, fourth coupled CMOS transistors **122C** while signal RSTB2 **118** is connected to second connection node **122B**.

[0033] DCC **100** also includes a correction stage **124** that is coupled to the first control stage **108**, second control stage **122**, and an input of signal CLK\_IN **114**. Correction stage **124** includes a first PMOS transistor **124A**, a second PMOS transistor **124B**, a first NMOS transistor **124C**, and a second NMOS transistors **124D**. As shown in FIG. **1**, transistors **124A-124D** are coupled in series. Also as shown in FIG. **1**, first PMOS transistor **124A** is coupled to a power node, which in some embodiments may be the same node as PWD\_DCC **106**. And second NMOS transistors **124D** is connected to a ground node. The gate of first PMOS transistor **124A** is coupled to drain/sources of first coupled CMOS transistors **108A** and second coupled CMOS transistors **108C**. The gate of first NMOS transistor **124C** is coupled to drain sources of third coupled CMOS transistors **122A** and fourth coupled CMOS transistors **122C**. Further, the gates of second PMOS transistor **124B** and first NMOS transistor **124C** are shorted, as shown in FIG. **1**, and the shorted gates are coupled to receive signal CLK\_IN **114**. As shown in FIG. **1**, second PMOS transistor **124B** and first NMOS transistor **124C** provide an output of correction stage **124**. For example, drain/source nodes of second PMOS transistor **124B** and first NMOS transistor **124C** provide an output of the correction stage **124**. This configuration of correction stage **124** may operate as a buffer and/or charge pump to modify the CLK\_IN **114** signal. Correction stage **124** may also be configured to be an integrator and/or modifier of CLK\_IN **114**.

[0034] An output of correction stage **124** is coupled to a series of inverters that result in an output signal CLK\_OUT **136**. For example, as shown in FIG. **1** the output of correction stage **124** (drain/source nodes of transistors with shorted gates) is connected to a first inverter **126**. The output of first inverter **126** may provide a differential output. In some embodiments, the output of first inverter **126** may be used as feedback by being routed to CKP **102**. First inverter **126** is connected in series with a second inverter **128**. The output of second inverter **128** may also be used as feedback in series with routed to CKN **104**.

[0035] DCC **100** also includes a third inverter **130** connected in series with second inverter **128**. But unlike first inverter **126** and second inverter **128**, the output of third inverter **130** is the output of DCC **100**.

[0036] In some embodiments, inverters **126**, **128**, and **130** may be configured to also provide gain and/or attenuation. Further, in some embodiments, inverters **126**, **128**, and **130** may be implemented with amplifiers similar to amplifier **200**, which is further discussed in connection with FIG. **2**.

[0037] FIG. **2** shows a circuit diagram of an exemplary implementation of amplifier **200** in accordance with some embodiments of the present disclosure. As discussed in connection with FIG. **1**, in some embodiments amplifier **200** is part of DCC **100**. For example, amplifier **200** can be used to receive differential clock signals for duty cycle modifications and/or corrections. However, amplifier **200** may be employed in other applications unrelated to DCC **100**. For example, amplifier **200** may be employed as a differential amplifier, as an inverter amplifier (such as first inverter **126** in FIG. **1**), and as a non-inverter amplifier. In some embodiments, as shown in FIG. **2**, amplifier **200** is configured as a folded cascode amplifier. But in other embodiments, elements of

amplifier **200** may be reconfigured to have non-folded cascode configurations.

[0038] Amplifier **200** includes a positive biasing circuit **210** and a negative biasing circuit **230**. Amplifier **200** also includes a differential input circuit **220**. Amplifier **200** further includes a first stage **250** and second stage **260**, which jointly create an amplification circuit **280** that provides the differential amplification in amplifier **200**.

[0039] Positive biasing circuit **210** may provide voltages and/or currents for the operation of amplifier **200**. As shown in FIG. 2, positive biasing circuit **210** includes a plurality of PMOS transistors. In other embodiments, however, positive biasing circuit **210** may have alternative transistors, such as BJT transistors and/or NMOS transistors.

[0040] The transistors in positive biasing circuit **210** include a first bias PMOS transistor **211**, a second bias PMOS transistor **213**, and a drive PMOS transistor **212**. As further discussed below in connection with FIGS. 3A, 3B, and 7, drive PMOS transistor **212** may be configured to be biased in a subthreshold region. A PMOS transistor **212** threshold voltage of drive PMOS transistor **212** may be determined by MOSFET threshold voltage equations such as

$$V_{sub.t} = V_{sub.FB} + 2\phi_{sub.f} + \sqrt{2\epsilon_{sub.s} q N_{sub.a} (2\phi_{sub.f} + V_{sub.SB})} / C_{sub.ox}$$
where  $V_{sub.t}$  is the threshold voltage,  $V_{sub.FB}$  is the transistor flat band voltage,  $\phi_{sub.f}$  is the surface potential,  $\epsilon_{sub.s}$  is the relative permittivity,  $q$  is elementary charge,  $N_{sub.a}$  is the doping concentration,  $V_{sub.SB}$  is the source-to-body substrate bias, and  $C_{sub.ox}$  is the effective capacitance. The dimensions, doping characteristics, and processing of drive PMOS transistor **212** may be selected to have drive PMOS transistor **212** operate in a subthreshold region when amplifier **200** is turned on. In some embodiments, for example, the  $W/D$ ,  $C_{sub.ox}$ , doping, and  $V_{sub.FB}$ , in PMOS transistor **212** are selected for subthreshold operation in amplifier **200**.

[0041] As shown in FIG. 2, the gates of first bias PMOS transistor **211**, second bias PMOS transistor **213**, and drive PMOS transistor **212** are directly connected. Further, first bias PMOS transistor **211**, second bias PMOS transistor **213**, and drive PMOS transistor **212** in positive biasing circuit **210** are connected to a power node **214** which provides a voltage and/or current supply. For example, in some embodiments power node **214** may be the same node as PWD\_DCC **106** (FIG. 1). First bias PMOS transistor **211**, second bias PMOS transistor **213**, and drive PMOS transistor **212** in positive biasing circuit **210** are also connected to other stages or devices in amplifier **200**. For example, first bias PMOS transistor **211** and drive PMOS transistor **212** may be connected to differential input circuit **220** and first stage **250**.

[0042] FIG. 2 shows an embodiment of positive biasing circuit **210** with three PMOS transistors. Other embodiments, not shown, may use alternative configurations of transistors in positive biasing circuit **210**. For example, positive biasing circuit **210** may include four or more transistors which may include both CMOS or BJT transistors. Alternatively, or additionally, positive biasing circuit **210** may include alternative three-terminal devices such as vacuum tubes or other semiconductor devices.

[0043] Similar to positive biasing circuit **210**, negative biasing circuit **230** includes transistors directly connected to differential input circuit **220**. But instead of being connected to first stage **250**, transistors in negative biasing circuit **230** are also connected to second stage **260**. Further, transistors in negative biasing circuit **230** include a plurality of NMOS transistors. In other embodiments, however, negative biasing circuit **230** may have alternative transistors. For example, negative biasing circuit **230** may include four or more transistors which may include both CMOS and BJT transistors. Alternatively, or additionally, negative biasing circuit **230** may alternatively include three-terminal devices such as vacuum tubes or other semiconductor devices.

[0044] The transistors in negative biasing circuit **230** include a drive NMOS transistor **232**, a first biasing NMOS transistor **231**, and a second biasing NMOS transistor **233**. Similar to drive PMOS transistor **212**, drive NMOS transistor **232** may be configurable to be biased in the subthreshold region. For example, dimensions, oxide, doping, and biasing circuitry of drive NMOS transistor **232** may be selected for biasing in the subthreshold region when amplifier **200** is turned on or

operated. In some embodiments, for example, the W/D, C.sub.ox, doping, and V.sub.FB, in NMOS transistor **232** are selected for subthreshold operation in amplifier **200**.

[0045] As shown in FIG. 2, the gates of drive NMOS transistor **232**, first biasing NMOS transistor **231**, and second biasing NMOS transistor **233**, have shorted gates. Further, transistors in negative biasing circuit **230** are connected to a ground node **234**. In some embodiments ground node **234** may be the same node as ground nodes in DCC **100**. Drive NMOS transistor **232**, first biasing NMOS transistor **231**, and second biasing NMOS transistor **233** are also connected to other stages or transistors in amplifier **200**. For example, some of the transistors of negative biasing circuit **230** may be connected to differential input circuit **220** and second stage **260**.

[0046] Differential input circuit **220** includes a plurality of transistors that are connected to one of first amplifier input VIP **202** or second amplifier input VIN **204**. In some embodiments, VIP **202** and VIN **204** may be connected to external elements. For example, VIP **202** and VIN **204** may be coupled to capacitors and/or resistors and receive input signals. In some embodiments, as shown in FIG. 1, inputs of amplifier **200** VIP **202** and VIN **204** receive signals CKP **102** and CKN **104**, respectively.

[0047] As shown in FIG. 2, the transistors in differential input circuit **220** include both NMOS and PMOS transistors. For example, differential input circuit **220** includes NMOS transistors **222A** and **222B** and PMOS transistors **224A** and **224B**. NMOS transistors **222A** and **222B** may be matching transistors. That is, NMOS transistors **222A** and **222B** may have the same dimensions, C.sub.ox, doping, and biasing circuitry. Further, NMOS transistors **222A** and **222B** may be configured to operate in the same biasing region and under similar voltage and current conditions. In other embodiments, however, NMOS transistors **222A** and **222B** may be independent and be configured with different W/Ds or different biasing circuitry configurations.

[0048] Like the NMOS portion of differential input circuit **220**, PMOS transistors **224A** and **224B** may also be matching transistors. For example, PMOS transistors **224A** and **224B** may have the same dimensions, C.sub.ox, doping, and biasing circuitry. And PMOS transistors **224A** and **224B** may be configured to operate in the same biasing or similar biasing regions. In other embodiments, however, PMOS transistors **224A** and **224B** may be independent and be configured with different W/Ds or different biasing circuitry configurations.

[0049] As shown in FIG. 2, the gate of each of NMOS transistor **222A** and PMOS transistor **224A** is coupled to VIP **202**. In contrast, the gate of each of NMOS transistor **222B** and PMOS transistor **224B** is coupled to VIN **204**. The resulting differential input configuration enables reception of a differential signal to be amplified. For example, in some embodiments VIP **202** and VIN **204** may respectively correspond to CKP **102** and CKN **104** from DCC **100** (FIG. 1). In such embodiments, differential input circuit **220** may interface to the inputs and/or feedback in DCC **100**.

[0050] Moreover, the drain/source of transistors in differential input circuit **220** are directly connected to other elements of amplifier **200**. For example, NMOS transistor **222A** is directly connected to drive PMOS transistor **212** and NMOS transistor **222B**. In turn NMOS transistor **222B** is directly connected to a PMOS in positive biasing circuit **210**. PMOS transistors **224A** and **224B** are both directly connected to first biasing PMOS transistor **211** in positive biasing circuit **210** while PMOS transistor **224A** is directly connected to drive NMOS transistor **232** and first biasing NMOS transistor **231** in negative biasing circuit **230**.

[0051] FIG. 2 shows a configuration of differential input circuit **220** with two NMOS and two PMOS transistors. But other configurations are possible for differential input circuit **220**. For example, differential input circuit **220** may be implemented with BJT transistors. Alternatively, or additionally, differential input circuit **220** may be implemented with other three-terminal devices. Moreover, instead of four transistors, differential input circuit **220** may have different arrangements that include more transistors, unpaired transistors, and/or a mix of transistor types. Further, differential input circuit **220** may connect to other elements in amplifier **200** to enable capturing a differential input to be amplified. For example, as shown in FIG. 2, differential input circuit **220** is

coupled to positive biasing circuit **210** and negative biasing circuit **230**.

[0052] First stage **250** is coupled to positive biasing circuit **210** and second stage **260** through a resistive element **270**. First stage **250** includes PMOS transistors **254**, which include a first PMOS transistor **254A** and a second PMOS transistor **254B**. In some embodiments, first PMOS transistor **254A** and second PMOS transistor **254B** are matching transistors with the same dimensions, C.sub.ox, doping, and biasing circuitry. In other embodiments, first PMOS transistor **254A** and second PMOS transistor **254B** are independent transistors. First stage **250** also includes a first boosting stage **252**. As shown in FIG. 2, first boosting stage **252** is connected to the gates of PMOS transistors **254**. Further, drain/source nodes of PMOS transistor **254A** are connected in series with drive PMOS transistor **212** and to the gate of drive PMOS transistor **212**. PMOS transistor **254B** is directly connected between a drain/source of NMOS transistor **222B**, which is coupled to VIN **204**, and an output node **282** of amplifier **200**.

[0053] In addition to being connected to PMOS transistors **254**, first boosting stage **252** may also be directly connected to transistors in positive biasing circuit **210**. For example, first boosting stage **252** is also connected to a drain/source of drive PMOS transistor **212** and to a drain/source of a second biasing PMOS transistor **213** in positive biasing circuit **210**. Further, first boosting stage **252** can be directly connected to respective gates of first PMOS transistor **254A** and second PMOS transistor **254B**.

[0054] Second stage **260** has a configuration similar to that of first stage **250**. But instead of being coupled to positive biasing circuit **210**, second stage **260** is coupled to negative biasing circuit **230**. Further, instead of having PMOS transistors **254**, second stage **260** has NMOS transistors **264**. Second stage **260** includes NMOS transistors **264**, which include a first NMOS transistor **264A** and a second NMOS transistor **264B**. Second stage **260** also includes a second boosting stage **262**. Similar to first boosting stage **252**, second boosting stage **262** may be connected to the gates of NMOS transistors **264**. Further, the drain/source of NMOS transistor **264A** is connected in series with drive NMOS transistor **232** and the gate of drive NMOS transistor **232**. NMOS transistor **264B** is directly connected to a drain/source of second biasing NMOS transistor **233** in negative biasing circuit **230** and to PMOS transistor **254B**. The shared node between PMOS transistor **254B** and NMOS transistor **264B** creates output node **282**.

[0055] In addition to being connected to NMOS transistors **264**, second boosting stage **262** is also directly connected to transistors in negative biasing circuit **230**. Second boosting stage **262** is also connected to a drain/source of drive NMOS transistor **232** and to a drain/source of second biasing NMOS transistor **233** in negative biasing circuit **230**.

[0056] As shown in FIG. 2, first stage **250** connects to second stage **260** via resistive element **270**. In particular, a drain/source of PMOS transistor **254A** is directly connected to resistive element **270** which is connected to a drain source of NMOS transistor **264A**. Further, resistive element **270** is also connected to gates of drive PMOS transistor **212** and drive NMOS transistor **232**. Specifically, as shown in FIG. 2, resistive element **270** connects to PMOS transistor **254A** and to the gate of drive PMOS transistor **212** at the same node. Thus, a gate of drive PMOS transistor **212** is directly connected to a first terminal of resistive element **270**. In particular, in some embodiments a gate of drive NMOS transistor **232** is directly connected to a second terminal of resistive element **270**. And resistive element **270** connects to NMOS transistor **264A** and to the gate of drive NMOS transistor **232** at the same node, which is different from the node connecting to drive PMOS transistor **212**.

[0057] Resistive element **270** is shown in FIG. 2 as a two-terminal element, which may include a resistor, capacitor, or inductor (or any combination thereof). But in some embodiments, resistive element **270** may comprise a different type of device. For example, resistive element **270** may include a three-terminal device, such as a transistor or a controlled diode. For example, resistive element **270** may include a transistor biased in a triode mode. In such embodiments, resistive element **270** may be coupled to receive a control signal that allows the selection of a specific resistance desired for operation of amplifier **200**. For example, in certain embodiments resistive



element **270** may be dynamically configured based on the operation of other elements in amplifier **200**. Further, in some embodiments, as further discussed in connection with FIG. **4B**, resistive element **270** includes: a PMOS transistor, a resistor, and an NMOS transistor, wherein the PMOS transistor is connected to the resistor in series and the resistor is connected in series with the NMOS transistor.

[0058] The inclusion of resistive element **270** shown in FIG. **2** enables configuring amplifier **200** for a self-biased gain-boosted operation. For example, resistive element **270** may be selected to place each of drive PMOS transistor **212** and drive NMOS transistor **232** in subthreshold region operation. Thus, in certain embodiments a value of the resistive element **270** may be selected to set a gate voltage of drive NMOS transistor **232** for operation in the subthreshold region and to set a gate voltage of drive PMOS transistor **212** for operation in the subthreshold region. By properly selecting transistors in amplifier **200**, and the value of resistive element **270**, one or more of the transistors in amplifier **200** can operate in the subthreshold region. This configuration results in several advantages for amplifier **200**. For example, by operating in the subthreshold region amplifier **200** requires a lower power voltage (or V<sub>dd</sub>) compared to other amplifiers. Also, by operating in the subthreshold region amplifier **200** achieves a higher DC gain compared to other amplifiers. In particular, the use of gain-boosted stages in amplifier **200** enable a DC gain higher than those of other amplifiers.

[0059] In addition to an increased DC gain, amplifier **200** (as shown in FIG. **2**) provides other operational advantages. For example, when compared with other folded cascode amplifiers, amplifier **200** reduces the number of external biasing voltages. Folded cascode configurations require a large number of external bias voltages. This requirement results in several constraints, particularly when the amplifier is fabricated in an integrated circuit. For example, having multiple biasing voltages results in area and power overhead, and susceptibility of cross-talk between biasing lines and/or noise. And given the relationship between amplifier gain and sensitivity to noise, the gain of other folded cascode amplifiers is limited by practical considerations of signal-to-noise ratios (SNRs). The configuration of amplifier **200** addresses these issues by providing a low voltage (e.g., less than 2.5V), self-biased, and gain-boosted amplifier. The use of resistive element **270** between first stage **250** and second stage **260** (each with its respective boosting stage), enables the operation of transistors in the subthreshold region, improving the amplifier gain and reducing the number of external biasing lines, which translates into a smaller footprint, less noise, and lower power consumption.

[0060] Moreover, the detailed configuration of amplifier **200** may also modify the gain spectrum as compared with other operational amplifiers. By having resistive element **270** placing drive NMOS transistor **232** and drive PMOS transistor **212** in the subthreshold region, it is possible to improve the dynamic range of amplifier **200**, allowing it to have strong gains at both low and high input or output voltages. For example, the configuration shown in amplifier **200** results in greater gains at low input voltages (e.g., input voltages of less than 100 mV), but also have high gains for high input voltages (e.g., above 500 mV).

[0061] In addition to improvements in operational performance, the configuration of amplifier **200** also improves requirements for fabrication. For example, as further discussed in connection to FIGS. **9A** and **9B**, the configuration of circuits and stages shown in FIG. **2** allows the configuration of specific areas with smaller footprint, simpler wiring, and lower power consumption. Further, the design of amplifier **200** is versatile and can be used in multiple technology nodes. For example, amplifier **200** may be implemented in various manufacturing processes including 3 nm, 5 nm, 7 nm, 10 nm, 16 nm, and 20 nm processes.

[0062] The operational and manufacturing advantages provided by amplifier **200** makes it a good candidate for an operational amplifier in digital and/or analog circuits. For example, amplifier **200** may improve the operation and/or facilitate the fabrication of DCC **100**.

[0063] FIG. **3A** shows a circuit diagram of an exemplary configuration **300** of drive transistors

implementing a resistor as resistive element **270**, in accordance with some embodiments of the present disclosure. In configuration **300**, resistive element **270** is implemented as a resistor **302**. As shown in FIG. **3A**, employing resistor **302** as the resistive element creates a branch of amplification circuit **280** (FIG. **2**) in which the gate of drive PMOS transistor **212** is coupled to one end of resistor **302** while the gate of drive NMOS transistor **232** is coupled to the other end of resistor **302**. Further, resistor **302** is also connected to transistors of first stage **250** and second stage **260**. Particularly, one end of resistor **302** is coupled to PMOS transistor **254A** and the other end of resistor **302** is coupled to NMOS transistor **264A**.

[0064] Configuration **300**, using resistor **302**, effectively decreases the gate-to-source voltages of drive NMOS transistor **232** and drive PMOS transistor **212** so that both can operate in the subthreshold region. That is, the incorporation of resistor **302** in a branch of amplification circuit **280** results in lower gate-source voltages in drive transistors, such lower voltages facilitating operation in subthreshold and permit self-biasing. Thus, adequately selecting the value of resistor **302** may result in the advantages of amplifier **200** as described above.

[0065] FIG. **3B** shows a circuit diagram of an exemplary configuration **350** of drive transistors implementing a transistor as resistive element **270**, in accordance with some embodiments of the present disclosure. In configuration **350**, resistive element **270** is implemented as a transistor **304**. As shown in FIG. **3B**, in some embodiments transistor **304** is a PMOS device. In other embodiments, however, transistor **304** may be an NMOS device or a BJT device. Transistor **304** may be used as a controlled variable resistor. For example,  $V_b$  applied to the gate of transistor **304** may be selected to place transistor **304** in a resistive or triode operation mode. The equivalent resistance may be selected to place drive PMOS transistor **212** and drive NMOS transistor **232** in the subthreshold region. Using transistor **304** as the resistive element creates a branch of amplification circuit **280** (FIG. **2**) in which the gate of drive PMOS transistor **212** is coupled to the source of transistor **304** while the gate of drive NMOS transistor **232** is coupled to the drain transistor **304**. Further, transistor **304** is also connected to transistors of first stage **250** and second stage **260**. Particularly, the source of transistor **304** is coupled to PMOS transistor **254A** and the drain of transistor **304** is coupled to NMOS transistor **264A**.

[0066] In configuration **350** the biasing condition of transistor **304** may be selected to decrease the gate-to-source voltages of drive NMOS transistor **232** and drive PMOS transistor **212** so that both of them can operate in the subthreshold region. That is, the incorporation of transistor **304** with  $V_b$  applied for triode operation results in adjusted gate-source voltages in drive transistors, which facilitate operation in subthreshold and permit self-biasing. Thus, appropriately selecting the value and biasing of transistor **304** results in the advantages of amplifier **200** as described above.

[0067] FIG. **3C** shows a circuit diagram of an exemplary configuration **380** of drive transistors implementing a diode as resistive element **270**, in accordance with some embodiments of the present disclosure. In configuration **380**, resistive element **270** is implemented as a diode **306**. Diode **306** may be a standard diode connected for forward biasing and a selected diode voltage drop required for resistive operation. In other embodiments, however, diode **306** may be configured for reverse bias and the breakdown voltage may be selected for an equivalent resistance. In some embodiments, diode **306** may be implemented with Zener and/or Schottky diodes. The equivalent resistance of diode **306** may be selected to place drive PMOS transistor **212** and drive NMOS transistor **232** in the subthreshold region. Using diode **306** as a resistive element creates a branch of amplification circuit **280** (FIG. **2**) in which the gate of drive PMOS transistor **212** is coupled to one end of diode **306** while the gate of drive NMOS transistor **232** is coupled to the other end of diode **306**. Further, diode **306** is also connected to transistors of first stage **250** and second stage **260**. Particularly, one end of diode **306** is coupled to PMOS transistor **254A** and another end of diode **306** is coupled to NMOS transistor **264A**.

[0068] In configuration **380** the biasing condition of diode **306** may be selected to decrease the gate-to-source voltages of drive NMOS transistor **232** and drive PMOS transistor **212** so that both

of them can operate in the subthreshold region. That is, the incorporation of diode **306**, with adequately selected equivalent resistance (either in forward or reverse modes) results in adjusted gate-to-source voltages in drive transistors, which facilitate operation in subthreshold and permit self-biasing. Thus, appropriately selecting the parameters of diode **306** may result in the advantages of amplifier **200** as described above.

[0069] FIG. **4A** shows a circuit diagram of an exemplary configuration **400** of a portion of amplifier **200** using variable resistors, in accordance with some embodiments of the present disclosure. In configuration **400**, resistive element **270** is implemented with a series of variable and fixed resistors. Such configuration may facilitate selection of adequate resistive values that result in subthreshold biasing of drive PMOS transistor **212** and drive NMOS transistor **232**.

[0070] In configuration **400**, resistive element **270** is implemented with a first variable resistor **402**, a fixed resistor **404**, and a second variable resistor **406**. This configuration allows to both increase and decrease of gate-to-source voltages ( $V_{gs}$ ) of drive PMOS transistor **212** and drive NMOS transistor **232** resulting in a more accurate control of gain and power consumption by precisely selecting the operation modes of drive transistors. Further, use of variable resistors as part of resistive element **270** enables increasing amplifier **200** output and common mode range.

[0071] The ability to accurately control the gate-to-source voltage of drive PMOS transistor **212** and drive NMOS transistor **232** allows the selection of  $V_{gs}$  based on the output voltage ( $V_O$ ) at output node **282**. To place drive PMOS transistor **212** and drive NMOS transistor **232** in the subthreshold region, configuration **400** allows adjusting  $V_{gs}$  based on  $V_O$ . For example, as further discussed in connection with FIG. **4B**, a signal from  $V_O$  may be employed as feedback control to dynamically adjust the value of first variable resistor **402** and second variable resistor **406**. In this way, as  $V_O$  at output node **282** increases, first variable resistor **402** and second variable resistor **406** may be modified to increase  $V_{gs}$ , avoid saturation, or triode operation, and maintain the transistor in the subthreshold region. Inversely, as  $V_O$  decreases, first variable resistor **402** and second variable resistor **406** may be adjusted to decrease  $V_{gs}$  to avoid saturation or triode operation and keep the device in the subthreshold region.

[0072] In some embodiments, first variable resistor **402** and second variable resistor **406** may be implemented with transistors similar to transistor **422** (as further discussed in connection with FIG. **4B**). In other embodiments, however, first variable resistor **402** and second variable resistor **406** may be implemented with alternative devices that allow control of their resistive values.

[0073] FIG. **4B** shows a circuit diagram of an exemplary configuration **450** of operational amplifier **200** using transistors as variable resistors in accordance with some embodiments of the present disclosure. In configuration **450**, the resistive element **270** is implemented with a PMOS transistor **422**, resistor **404**, and an NMOS transistor **426**. Configuration **450** shows an implementation of configuration **400** in which the variable resistors are implemented using transistors. Thus, in some embodiments, as shown in FIG. **4B**, first variable resistor **402** and second variable resistor **406** (FIG. **4A**) are implemented with PMOS transistor **422** and NMOS transistor **426** respectively. Configuration **450** uses a combination of PMOS and NMOS transistors to facilitate manufacturing of resistive element **270** and create self-biasing based on  $V_O$  at output node **282**. But other configurations are also possible using both only NMOS or PMOS transistors, or different types of devices (e.g., BJT).

[0074] In configuration **450**, the gates of PMOS transistor **422** and NMOS transistor **426** are directly connected to output node **282**. This configuration creates a feedback through PMOS transistor **422** and NMOS transistor **426**. With this configuration **450**, when amplifier **200** output  $V_O$  is low, the PMOS transistor **422** resistance will decrease while the NMOS transistor **426** resistance will increase. And when NMOS transistor **426** resistance increase, the NMOS transistor **232**/NMOS transistor **233**  $V_{gs}$  further decreases and the over-drive voltage ( $V_{ov}$ ), defined as the voltage between gate-to-source ( $V_{gs}$ ) in excess of the threshold voltage, of NMOS transistor **233** will also decrease. This type of feedback in resistive element **270** enables accurate control of the

gain and dynamic, self-biasing adjustments to maintain a target DC gain and dynamic range. [0075] PMOS transistor **422** and NMOS transistor **426** in configuration **450** may be implemented with finFETs. For example, PMOS transistor **422** may be implemented with three finFETs coupled in parallel, each of the finFETs having  $L=8n$  and  $M=24$ , where  $L$  defines the transistor length based on the selected process node and  $M$  defines the transistor type. Similarly, NMOS transistor **426** may be implemented with three finfets coupled in parallel each of the finFETs having  $L=8n$  and  $M=24$ . In such embodiments, the value of resistor **404** may be in the kilo-ohms range. For example, resistor **404** may be between 1-100 K $\Omega$ . For example, resistor **404** may have a 1.8 K $\Omega$  value.

[0076] FIG. 5A shows an exemplary circuit diagram of first boosting stage **252** in accordance with some embodiments of the present disclosure. First boosting stage **252** provides additional gain to amplifier **200**. As described in connection with FIG. 2, first boosting stage **252** may be within first stage **250** (FIG. 2).

[0077] First boosting stage **252** includes a first input substage **512**. First input substage **512** includes input PMOS transistors **506A** and **506B**. One of the source/drain nodes of PMOS transistors **506A** and **506B** is directly connected and coupled to power node **214**. The opposite source/drain nodes of PMOS transistors **506A** and **506B** are connected to a first output VOPN **506** and a second output VOPP **508**. The gates of PMOS transistors **506A** and **506B** are coupled to a first input VPP **502** and a second input VPN **504**. In some embodiments, the of inputs PMOS transistors within first input substage **512** may be matched, having the same dimensions, biasing, and operation. In other embodiments, however, the input PMOS transistors within first input substage **512** may be independent.

[0078] First boosting stage **252** also includes a first loading substage **510**. First loading substage **510** includes NMOS transistors **507A** and **507B** that are connected to PMOS transistors **506A** and **506B** in first input substage **512** and to ground node **234**. For example, first input substage **512** may include PMOS transistors **506A** and **506B** coupled to power node **214**. Further, the gates of NMOS transistors **507A** and **507B** are shorted and they may be connected to an input node VB1. Similarly as discussed in connection with FIG. 3B, the input of node VB1 may be selected to place NMOS transistors **507A** and **507B** in a triode region to act as an active load. The effective impedance value of the loading substage **510** may be selected based on the desired gain, SNR, dynamic range, or a combination of these parameters. The first loading substage **510** embodiment of FIG. 5A, however, is one option and alternative embodiments are discussed below in connection with FIGS. 6A-6E.

[0079] FIG. 5B shows an exemplary circuit diagram of second boosting stage **262** in accordance with some embodiments of the present disclosure. Second boosting stage **262** provides additional gain to amplifier **200**. As described in connection with FIG. 2, second boosting stage **262** may be within first stage **260** (FIG. 2).

[0080] Second boosting stage **262** includes a second input substage **532**. Second input substage **532** includes input NMOS transistors **533A** and **533B**. One of the source/drain nodes of the input. NMOS transistors **533A** and **533B** within second input substage **532** is directly connected and coupled to ground node **234** (FIG. 2). For example, second input substage **532** can be coupled to drain/source nodes of each of NMOS transistors **264**, where the second loading substage is coupled to a gate nodes of each of NMOS transistors **533A** and **533B**. Additionally NMOS transistors **533A** and **533B** are coupled to ground node **234**.

[0081] The opposite source/drain nodes of input NMOS transistors **533A** and **533B** are connected to a first output VONP **526** and a second output VONN **528**. The gates of NMOS transistors **533A** and **533B** are coupled to a first input VNP **522** and a second input VNN **524**. In some embodiments, the input NMOS transistors within second input substage **532** may be matched, having the same dimension, biasing, and operation. In other embodiments, however, the input NMOS transistors within second input substage **532** may be independent.

[0082] Second boosting stage **262** also includes a second loading substage **530**. Second loading substage **530** includes PMOS transistors **531A** and **531B** that are connected to NMOS transistors

533A and 533B in the second input substage 532 and to power node 214. Further, the gates of PMOS transistors 531A and 531B in second loading substage 530 are shorted and they may be connected to an input node VB2. As discussed in connection with FIG. 3B, the input of VB2 may be applied to place PMOS transistors 531A and 531B in a triode region and act as an active load. The effective impedance value of the second loading substage 530 may be selected based on the desired gain, SNR, dynamic range, or a combination of these parameters.

[0083] FIGS. 6A-6E show circuit diagrams of exemplary boosting stages using different loading devices. Depending on the application, integrated circuit area restrictions, or power targets, a designer may elect different loading mechanisms or devices for boosting stages.

[0084] FIG. 6A shows a circuit diagram of an exemplary boosting stage 252A using a resistive load in accordance with some embodiments of the present disclosure. In boosting stage 252A of FIG. 6A, the loading substage uses passive loading with a loading resistor 642. Although loading resistor 642 is shown as a single resistor, loading resistor 642 may include a network of passive resistors.

[0085] FIG. 6B shows a circuit diagram of an exemplary boosting stage 252B using an inductive load in accordance with some embodiments of the present disclosure. In boosting stage 252B of FIG. 6B, the loading substage uses passive loading with a loading inductor 644. Although loading inductor 644 is shown as a single inductor, loading inductor 644 may include a network of inductors and/or capacitors with an equivalent impedance that is desired for the loading substage. In certain embodiments, boosting stages 252B can combine embodiments of FIGS. 6A and 6B having resistor 642 or inductor 644, or combinations thereof.

[0086] FIG. 6C shows a circuit diagram of an exemplary boosting stage 252C using an active load in accordance with some embodiments of the present disclosure. In boosting stage 252C of FIG. 6C, the loading substage uses active loading with a loading transistor 646. Although loading transistor 646 is shown as a single device, loading transistor 646 may include a network of transistors. For example, a possible implementation of boosting stage 252C of FIG. 6C is first loading substage 510 that uses back-to-back transistors. Similarly, other embodiments may include networks of transistors coupled in parallel, series, or a combination of parallel and series.

[0087] FIG. 6D shows a circuit diagram of an exemplary boosting stage 252D using an active PMOS diode load in accordance with some embodiments of the present disclosure. In boosting stage 252D of FIG. 6D, the loading substage uses active loading with a PMOS diode 648. Although PMOS diode 648 is shown as a single MOS device with a shorted gate, PMOS diode 648 may include a network of transistors or standard diodes (not CMOS) or Zener and/or Schottky diodes.

[0088] FIG. 6E shows a circuit diagram of an exemplary boosting stage 252E using an active NMOS diode load in accordance with some embodiments of the present disclosure. In boosting stage 252E of FIG. 6E, the loading substage uses active loading with an NMOS diode 650. Although NMOS diode 650 is shown as a single MOS device with a shorted gate, NMOS diode 650 may include a network of transistors or standard diodes (not CMOS), including (for example) Zener and/or Schottky diodes.

[0089] FIG. 7 shows a circuit diagram of a first exemplary amplifier 700 with active loads and resistive coupling for subthreshold biasing in accordance with some embodiments of the present disclosure. Amplifier 700 embodies a possible implementation of amplifier 200. Like amplifier 200, amplifier 700 also includes differential input circuit 220, positive biasing circuit 210, negative biasing circuit 230, amplification circuit 280 (including first stage 250 and second stage 260), and resistive element 270 between first stage 250 and second stage 260. However, in amplifier 700 first boosting stage 252 (within the first stage 250) is implemented with the boosting stage shown in FIG. 5A, second boosting stage 262 (within second stage 260) is implemented with the boosting stage shown in FIG. 5B, and resistive element 270 is implemented with resistor 302 (FIG. 3).

[0090] As shown in FIG. 7, the resulting circuit includes a plurality of direct connections between the different transistors in amplifier 700. For example, as shown in FIG. 7 one end of resistive element 270 is directly connected to a transistor in first stage 250 (e.g., PMOS transistor 254A), a

gate of drive PMOS transistor **212**, and to gates of loading transistors in the second boosting stage (e.g., transistors in loading substage **530**). The opposite end of resistive element **270** is directly connected to a transistor in the second stage **260** (e.g., NMOS transistor **264A**), a gate of drive NMOS transistor **232**, and also to gates of loading transistors in the first boosting stage (e.g., transistors in loading substage **510**). Further, a gate of PMOS transistor **254A** is directly connected to drain/source nodes of transistors in the first boosting stage **252**. In addition, a gate of NMOS transistor **264A** is directly connected to drain/source nodes of transistors in the second boosting stage **262**. Thus, amplifier **700** can be configured so that a gate of drive PMOS transistor **212** is directly connected to a first terminal of resistive element **270**, and a gate of drive NMOS transistor **232** is directly connected to a second terminal of resistive element **270**. In such configuration, the first terminal of resistive element **270** is directly connected to second loading substage **530** and second terminal of resistive element **270** is directly connected to first loading substage **510**.

[0091] FIG. **7** also shows connections between transistors in the first input substage **512** and the second input substage **532** and other elements of amplifier **700**. For example, as shown in FIG. **7** gates of first input substage **512** are connected to drain source nodes of positive biasing circuit **210**. And gates of second input substage **532** are connected to drain source nodes of negative biasing circuit **230**. Moreover, the gate of PMOS transistor **254B** is directly connected to drain/source nodes of transistors in the first boosting stage **252**. In addition, a gate of NMOS transistor **264B** is directly connected to drain/source nodes of transistors in the second boosting stage **262**.

[0092] Amplifier **700** shows an implementation of amplifier **200** in which the boosting substages use active loading and resistive element **270** uses a passive load. This type of implementation may be employed to improve control of the boosting stages while minimizing power and area expenditures for coupling between first stage **250** and second stage **260**.

[0093] FIG. **8** shows a circuit diagram of a second exemplary amplifier **800** with subthreshold biasing using a coupling resistor in accordance with some embodiments of the present disclosure. Amplifier **800** embodies an alternative implementation of amplifier **200** that does not use boosting stages and places the coupling resistive element between stages at a different node. Amplifier **800** still places drive NMOS transistor **232** in the subthreshold region by using a resistive element to couple stages of an amplification circuit. However, between different elements of the stages to avoid using the boosting stages and minimize a footprint and/or power consumption. This implementation, however, may result in narrower dynamic ranges.

[0094] Amplifier **800**, like amplifier **200**, includes positive biasing circuit **210**, negative biasing circuit **230**, and differential input circuit **220**. However, instead of having first stage **250** and second stage **260**, amplifier **800** has stages without boosting. Amplifier **800** has a first stage **810** including PMOS transistors **812** and a coupling NMOS transistor **814**. The PMOS transistors **812** include a PMOS transistor **812A** (which can be similar to PMOS transistor **254A**) and a PMOS transistor **812B** (which can be similar to PMOS transistor **254B**). However, instead of having first boosting stage **252**, first stage **810** includes coupling NMOS transistor **814**. The source/drain nodes of coupling NMOS transistor **814** are connected to power node **214** and a resistive element **830** respectively. Also, the gate of coupling NMOS transistor **814** is coupled to drive PMOS transistor **212** and PMOS transistor **812A**.

[0095] Amplifier **800** also has a second stage **820** including NMOS transistors **822** and a coupling PMOS transistor **824**. NMOS transistors **822** include an NMOS transistor **822A** (which can be similar to NMOS transistor **264A**) and an NMOS transistor **822B** (which may be similar to NMOS transistor **264B**). However, instead of having second boosting stage **262**, second stage **820** includes a coupling PMOS transistor **824**. The source/drain nodes of coupling PMOS **824** are connected to ground node **234** and resistive element **830**, respectively. Also, the gate of coupling PMOS **824** is coupled to drive NMOS transistor **232** and NMOS transistor **822A**.

[0096] Unlike first stage **250** and second stage **260**, which are coupled via resistive element **270** and output node **282**, first stage **810** and second stage **820** are coupled through resistive element

**830**, output node **282**, and other direct connections between elements of the stages. For example, as shown in FIG. **8**, NMOS transistor **822A** and PMOS transistor **824A** are directly connected (without resistive element **270** as in amplifier **200**). Also, the gates of PMOS transistors **812** are directly connected to each other (without the boosting stage) and they are connected to a drain/source node of NMOS transistor **822A**. Further, the gates of NMOS transistors **822** are directly connected to each other (without the boosting stage) and the gates are connected to a drain/source node of PMOS transistor **812A**.

[0097] In addition, first stage **810** and second stage **820** are connected through resistive element **830**. Resistive element **830** connects the coupling NMOS transistor **814** and the coupling PMOS **824**. The resistive element **830** is also directly connected to the gate of drive NMOS transistor **232**. Such configuration results in a biasing in the subthreshold region for drive NMOS transistor **232**. With an appropriately selected resistive element **830**, drive NMOS transistor **232** may be set in the subthreshold region. Resistive element **830** may be selected from the elements discussed above for resistive element **270**. That is, resistive element **830** may be implemented with passive, active, or combined loads. For example, resistive element **830** may be implemented simply with a resistor (see FIG. **3A**) or an inductive element. Resistive element **830**, however, may also be implemented with a transistor (see FIG. **3B**). Further, resistive element **830** may also be implemented with a diode (see FIG. **3C**).

[0098] The biasing configuration in amplifier **800** provides, at least partially, the advantages discussed above in connection of FIG. **2** because amplifier **800** also operates drive transistors in the subthreshold region. For example, amplifier **800** also achieves greater DC gain than conventional amplifiers and has the potential of operating at greater range of output voltages. Amplifier **800** can also be manufactured in a smaller area (because it has fewer transistors) and may be employed for applications that require lower power consumption. Circuit designers can combine embodiments of amplifiers **200**, **700**, and **800** based on gain, power, and area conditions and/or restrictions of specific applications.

[0099] FIG. **9A** shows an exemplary schematic of a first layout first floor plan **900** for an integrated circuit in accordance with some embodiments of the present disclosure. First floor plan **900** may be used to implement amplifier **200**, amplifier **700**, and/or amplifier **800**. First floor plan **900** includes a positive biasing area **902**. In some embodiments, positive biasing area **902** may include elements of positive biasing circuit **210**. Further positive biasing area **902** may also include elements of differential input circuit **220**, such as PMOS transistors **224A** and **224B**. In such embodiments, positive biasing area **902** includes drive PMOS transistor **212**. First floor plan **900** also includes a negative biasing area **908**. In some embodiments, negative biasing area **908** may include elements of negative biasing circuit **230**. In such embodiments, negative biasing area **908** includes drive NMOS transistor **232**. Further, negative biasing area **908** may also include elements of differential input circuit **220**, such as NMOS transistors **222A** and **222B**.

[0100] First floor plan **900** also includes an input area **905** which includes a p-input area **904** and a n-input area **906**. Input area **905** may include elements of differential input circuit **220**. For example, p-input area **904** may include PMOS transistors **224** and n-input area **906** includes NMOS transistors **222**.

[0101] First floor plan **900** also includes a first boosting area **910** and a second boosting area **912**. In some embodiments, first boosting area **910** may include elements of first stage **250**. In other embodiments, first boosting area **910** may include elements of first boosting stage **252** only (excluding, for example, PMOS transistors **254**). In some embodiments, second boosting area **912** may include elements of second stage **260**. In other embodiments, second boosting area **912** may include elements of second boosting stage **262** only (excluding, for example, NMOS transistors **264**).

[0102] First floor plan **900** also includes a resistive area **914**, which may include resistive element **270**. Alternatively, or additionally, resistive area **914** may include resistive element **830**. For

example, resistive area **914** may include resistor **302**, transistor **304**, or diode **306** (FIGS. 3A-3C). Further, resistive area **914** may connect between first boosting area **910** and second boosting area **912**.

[0103] First floor plan **900** shows a possible configuration of the different areas for amplifiers **200**, **700**, or **800**. As shown in FIG. 9, input area **905** is between positive biasing area **902** and negative biasing area **908**. In particular, while p-input area **904** neighbors and contacts positive biasing area **902**, n-input area **906** neighbors and contacts negative biasing area **908**. And p-input area **904** and n-input area **906** neighbor, contact, and/or are adjacent to each other.

[0104] In addition, in first floor plan **900**, first boosting area **910** neighbors, contacts, and/or is adjacent to both positive biasing area **902** and p-input area **904** on the same side of first boosting area **910**. Second boosting area **912** neighbors, contacts, and/or is adjacent to both negative biasing area **908** and n-input area **906** on the same side of second boosting area **912**. Also, first boosting area **910** and second boosting area **912** neighbor, contact, and/or are adjacent to each other on a side that is different than the side adjacent, neighboring, or contacting other areas of first floor plan **900**.

[0105] In first floor plan **900**, resistive area **914** neighbors, contacts, and/or is adjacent to both first boosting area **910** and second boosting area **912** on the same side of resistive area **914**. Further, as shown in first floor plan **900**, resistive area **914** may only neighbor first boosting area **910** and second boosting area **912**, being separated from input area **905**, positive biasing area **902**, and negative biasing area **908**.

[0106] Thus, as shown in FIG. 9A, an integrated circuit implementing disclosed amplifiers can be arranged so that positive biasing area **902** neighbors first boosting stage **910** and the p-input area **904**. Further, negative biasing area **908** neighbors the second boosting stage **912** and the n-input area **906**. Additionally, or alternatively, resistive area **914** neighbors the first boosting stage area **910** and the second boosting area **912**.

[0107] FIG. 9B shows an exemplary schematic of a second layout floor plan **920** for an integrated circuit in accordance with some embodiments of the present disclosure. Second floor plan **920** may be used to implement amplifiers **200**, **700**, and/or **800**.

[0108] Similar to first floor plan **900**, second floor plan **920** includes positive biasing area **902**, negative biasing area **908**, and input area **905** which includes p-input area **904** and n-input area **906**. However, unlike first floor plan **900**, second floor plan **920** combines boosting areas in a single boosting area **915**. While first floor plan **900** has first boosting area **910** and second boosting area **912**, second floor plan **920** has a single boosting area **915** which may combine elements of first stage **250** and second stage **260**. Alternatively, boosting area **915** may include elements of first boosting stage **252** and second boosting stage **262** only.

[0109] Combining boosting elements in boosting area **915** generates a different organization for second floor layout **920**. In second floor layout **920**, boosting area **915** is surround by other areas. For example, boosting area **915** neighbors on one side with input area **905**. On an opposite side, boosting area **915** neighbors with resistive area **914**. On a third side, boosting area neighbors, is adjacent, and/or contacts positive biasing area **902**. And on a fourth side, opposite to the third side, boosting area **915** neighbors, is adjacent, and/or contacts negative biasing area **908**. Further, in second floor layout **920**, resistive area **914** neighbors, contacts, and/or is adjacent to positive biasing area **902** and negative biasing area **908**, in addition to the input area **905**.

[0110] Other elements in second floor plan **920** have a similar disposition as in first floor plan **900**. For example, input area **905** is disposed between positive biasing area **902** and negative biasing area **908**, where p-input area **904** neighbors, contacts, and/or is adjacent to positive biasing area **902** while n-input area **906** neighbors, contacts, and/or is adjacent to negative biasing area **908**.

[0111] FIG. 10 shows a flow chart of an exemplary method **1000** for operation of an amplifier circuit in accordance with some embodiments of the present disclosure. In some embodiments, disclosed amplifiers **200**, **700**, and/or **800** may operate based on method **1000**. For example,



transistors in amplifier **200** may be biased, connected, and/or operated based on method **1000** to provide a gain at output node **282** when an input signal is inputted at first amplifier input VIP **202** and/or second amplifier input VIN **204**.

[0112] Method **1000** may initiate in step **1002**. In step **1002**, one or more PMOS transistors within a p-type wide-swing cascode current mirror of an amplifier circuit are configured for operation in a saturation region. For example, in step **1002**, first PMOS transistor **254A** may be biased in a saturation region. The PMOS transistors biased in saturation region in step **1002** may be connected to drive transistors of the amplifier. For example, in step **1002**, PMOS transistor **254A** may be biased for operation in saturation region while it is directly connected to drive PMOS transistor **212**.

[0113] In step **1004**, one or more NMOS transistors within an n-type wide-swing cascode current mirror of an amplifier circuit are configured for operation in a saturation region. For example, in step **1004**, first NMOS transistor **264A** may be biased so it operates in a saturation region. The NMOS transistors biased in saturation region in step **1004** may be connected to drive transistors of the amplifier. For example, in step **1004**, NMOS transistor **264A** may be biased for operation in saturation region while it is directly connected to drive NMOS transistor **232**.

[0114] In step **1006**, drive NMOS transistor **232** and drive PMOS transistor **212** are configured for operation in a subthreshold region. As further described above in connection with FIG. 2, a resistive element may couple NMOS with PMOS transistors in amplifier circuits. For example, in amplifier **200**, resistive element **270** connects first NMOS transistor **264A** and first PMOS transistor **254A**. This configuration will enable operating drive NMOS transistor **232** and drive PMOS transistor **212** in subthreshold. Without resistive element **270**, drive NMOS transistor **232** and drive PMOS transistor **212** could not be both operated in subthreshold regions because the gates of drive NMOS transistor **232** and drive PMOS transistor **212** would be connected together. But resistive element **270** can be used to decouple gates of drive NMOS transistor **232** and drive PMOS transistor **212**, allowing a configuration with both drive NMOS transistor **232** and drive PMOS transistor **212** operating in the subthreshold region.

[0115] In step **1008**, the amplifier circuit may be powered using a supply voltage. For example, amplifier **200** may be powered by inputting the supply voltage on power node **214**. The supply voltage may be selected based on the configuration of transistors in the amplifier, desired currents, and the biasing of transistors in steps **1002** and **1004**. For example, in some embodiments the supply voltage applied to power nodes of the amplifiers may be proportional to a sum of a voltage drops in drive transistors and in the resistive element. The supply voltage used to power amplifier **200** may also (or alternatively) be proportional to a sum of the voltage drop on drive NMOS transistor **232**, the voltage drop on resistive element **270**, and the voltage drop on drive PMOS transistor **212**. Further, in some embodiments, the selected supply voltage (VDD) may be equal to the sum of the voltage drop on drive NMOS transistor **232** ( $V_{gs\_232}$ ), the voltage drop on resistive element **270** ( $V_{r\_270}$ ), and the voltage drop on drive PMOS transistor **212** ( $V_{gs\_212}$ ). Thus, in some embodiments,  $VDD = V_{gs\_232} + V_{r\_270} + V_{gs\_212}$ . Further,  $V_{r\_270}$  can be set based on a current through drive NMOS transistor **232**, resistive element **270**, and drive PMOS transistor **212** as  $V_{r\_270} = I \cdot R$ , where  $I$  is the current and  $R$  is the equivalent resistance of resistive element **270**.

[0116] Moreover, the supply voltage (VDD) of step **1008** may also be selected based on the threshold voltage and overdrive conditions of transistors in the amplifier circuit. For example, in certain embodiments the supply voltage (VDD) may be selected to be at least two times the sum of a threshold voltage of transistors in the p- and n-types wide-swing cascode current mirrors ( $V_{sub.t}$ ) and an overdrive voltage ( $\Delta V$ ) of the transistors biased in saturation region. Thus, for such embodiments, in step **1006**  $VDD \geq 2 \cdot (V_{sub.t} + \Delta V)$ .

[0117] Steps **1002-1008** of method **1000** allow the configuration of a self-biased amplifier without external biases and without any degradation in its AC performance. The method enables the use of an amplifier circuit with enhanced gain that maintains a wide dynamic range.

[0118] In step **1010**, a signal may be inputted on a differential input circuit of the amplifier circuit. For example, in step **1010** a signal may be inputted on differential input circuit **220** of amplifier **200**. As discussed in connection with FIG. **1**, the differential input to amplifier **200** may be signal CKP **102** and signal CKN **104**.

[0119] The inputted signal is amplified by the amplifier circuit. And based on the configuration setup in steps **1002-1008**, the amplifier circuit produces an amplified output. Thus, in step **1012** the amplifier circuit may generate an output in an output node that is based on the differential input signal. For example, in step **1012** amplifier **200** may generate an output at output node **282**. As described in connection with FIG. **1**, the output generated by amplifier **200** may be used as a control signal in a DCC.

[0120] The gain generated by the amplifier circuit in step **1012** is based on a boosted gain stage and an input gain stage. The input gain stage may be based on the configuration of the differential input circuit **220**. For example, the input gain stage may be based on the transconductance of transistors in differential circuit **220**. In some embodiments, the input gain stage in amplifier **200** may be proportional to the transconductance of NMOS transistors **222** and PMOS transistors **224**. The boosted gain stage may be based on the configuration of amplification circuits. For example, the boosted gain stage may be based on the transconductance and output resistance of amplification circuit **280**. In some embodiments, the boosted gain stage in amplification circuit **280** may be based on the configuration of first boosting stage **252** and second boosting stage **262**. The boosted gain stage may be proportional to the transconductance of first input substage **512**, first loading substage **510**, second loading substage **530**, second input substage **532** and the output resistance of the amplification stages. In some embodiment the total gain of amplification circuit could be determined based on the gain of first boosting stage **252** ( $A_{vp}$ , based on the transconductance of first input substage **512**), and the gain of the second boosting stage ( $A_{vn}$ , proportional to the transconductance of second input substage **532**). The gain in these stages then determine equivalent resistances of first stage **250** ( $R_{250}$ ) and second stage **260** ( $R_{260}$ ). Specifically:

$$[00001] R_{250} = g_{213-254B} * r_{254B} (r_{213} / r_{222B}) * A_{vp},$$

where (i)  $g_{213-254B}$  is the combined transconductance in second bias PMOS transistor **213** and second PMOS transistor **254B**, (ii)  $r_{254B}$  is the output resistance for second PMOS transistor **254B**, (iii)  $r_{213}$  is the output resistance of second bias PMOS transistor **213**, (iv)  $r_{222B}$  is the output resistance of NMOS transistor **222B**, and (v)  $A_{vp}$  is the gain of first boosting stage **252**.

Further,

$$[00002] R_{260} = g_{233-264B} * r_{264B} (r_{233} / r_{224B}) * A_{vn},$$

where (i)  $g_{233-264B}$  is the combined transconductance in second biasing NMOS transistor **233** and second NMOS transistor **264B**, (ii)  $r_{264B}$  is the output resistance for second NMOS transistor **264B**, (iii)  $r_{233}$  is the output resistance of second biasing NMOS transistor **233**, (iv)  $r_{224B}$  is the output resistance of PMOS transistor **224B**, and (v)  $A_{vn}$  is the gain of second boosting stage **262**.

[0121] The equivalent resistances  $R_{250}$  and  $R_{260}$  of the boosting stages determine the total gain of the amplifier circuit, defined as

$$[00003] A_v = (g_{222} + g_{224}) (R_{250} / R_{260}),$$

[0122] where (i)  $g_{222}$  is the transconductance of NMOS transistors **222** and (ii)  $g_{224}$  is the transconductance of PMOS transistors **224**. Accordingly, in step **1012**, the amplifier circuit may generate an output that is proportional to  $A_{sub.v}$  and the differential input signal. In some embodiments, the amplifier circuit generates an output that multiplies the input signal and  $A_{sub.v}$  to generate an output that is equal to  $V_{sub.out} = A_{sub.v} * V_{sub.in}$ .

[0123] In some embodiments, method **1000** may include a step of adjusting the operational mode. For example, in step **1014**, drop voltages in drive transistors may be reduced to adjust the power supply. In step **1008**, the supply voltage is determined based on threshold voltages, overdrive voltages, and voltage drops. These voltages may be adjusted to, for example, reduce the supply

voltage for low power operations. Thus, in step **1014**, the amplifier circuit may initiate a low voltage application by reducing the supply voltage. For example, drive NMOS transistor **232** may be re-biased to have a lower voltage drop at the drive NMOS transistor **232**. Alternatively, or additionally, step **1014** of method **1000** may include reducing the overdrive voltage to operate under a low voltage application and increasing an output swing. Accordingly, method **1000** enables the adjustment of biasing statutes and the selection of currents in the wide-swing cascode current mirror to control the supply voltage and adjust for different operational modes.

[0124] The disclosed amplifiers, circuit configurations, and biasing conditions improve the operation of amplifiers and resolve technical challenges of other designs. Further, the disclosed configurations facilitate integrated circuit fabrication by, for instance, minimizing required external biases for the operational amplifier.

[0125] For example, disclosed amplifiers **200**, **700**, and/or **800** facilitate the operation and configuration of operational amplifiers by reducing the number of external bias voltages that are necessary to operate the circuit. The disclosed configuration of an amplifier with a positive biasing circuit, a negative biasing circuit, and amplifier circuit (with several stages and a resistive element) address drawbacks of conventional amplifiers. Conventional operational amplifiers (particularly folded cascode amplifiers) may use a large number of external bias voltages. Such large number of external bias voltages creates both performance and fabrication issues. For example, amplifiers with many external voltages require a larger fabrication area and consume more power (causing overheating issues). Further, amplifiers with a large number of external voltages may experience performance problems as they are more susceptible to noise, cross-talk, and high sensitivity to bias points and bias variations. The disclosed embodiments overcome these problems through a self-biasing configuration in which resistive elements self-bias transistors, resulting in fewer biasing nodes than in alternative approaches. Further, the disclosed embodiments allow self-biasing of transistors without degrading AC performance or the need to increase supply voltage.

[0126] In particular, the disclosed embodiments facilitate self-biasing of transistors in the circuit by utilizing resistive elements that self-bias the gain boost stages of the operational amplifier. The disclosed embodiments employ a resistive element (either active or passive) connected to gain boost stages and drive transistors. This configuration facilitates self-biasing of drive and boosting transistors. Further, as discussed in connection with FIG. 2, the resistive element (such as resistive element **270**) may be selected and coupled between gain boosting stages to place drive transistors in a subthreshold region. The subthreshold operation region of the drive transistors results in high DC gains without degrading AC performance and minimizes power consumption. The disclosed embodiments result in several advantages for both the operation and fabrication of operational amplifiers (and particularly folded cascode amplifiers). For example, the selection of a resistive element between boosting stages enables operating certain transistors of amplifiers **200**, **700**, or **800** in the subthreshold region, which reduces power requirements. Also, by operating in the subthreshold region, amplifiers of the disclosed embodiments achieve increased DC gain.

[0127] Moreover, in addition to increased DC gain, disclosed embodiments also provide other operational advantages. For example, disclosed embodiments facilitate fabrication of integrated circuits in smaller areas and with lower power consumption. Further, the disclosed amplifier circuits also improve the amplifier's stability and sensitivity to noise because while traditional folded cascode amplifiers have limited signal-to-noise ratios (SNRs)—in part due to the required biasing conditions—the disclosed self-biased configuration minimizes noise sources.

[0128] Thus, disclosed embodiments and circuit configurations provide a low voltage, self-biased, and gain-boosted amplifier. The use of resistive elements to self-bias transistors and operate in the subthreshold region improves the amplifier gain, reduces the number of external biasing lines, minimizes potential noise, and improves power consumption characteristics.

[0129] Moreover, disclosed embodiments also have a greater operational range. By including resistive elements for self-biasing and subthreshold region operation, the disclosed embodiments

improve the dynamic range of the amplifier, allowing it to have strong gains at both low and high output voltages. Other amplifiers have a gaussian gain, with a peak gain at average output voltages but low gain (or even attenuation) at low or high output voltages. For example, other amplifiers may have a peak gain at around  $V_O=350$  mV, but low gain for low output voltages (e.g.,  $V_O=100$  mV) or high output voltages (e.g.,  $V_O=650$  mV). In contrast, the disclosed embodiments and amplifier configurations result in a better amplification range, with high gain at the extremes of the output voltage. For example, disclosed embodiments achieve greater gains at low (e.g.,  $V_O=100$  mV) and high (e.g.,  $V_O=650$  mV) output voltages. Consistent with some of the disclosed configurations, amplifiers achieve 20 dB-30 dB of gain boost at the edges of the output voltage range when compared with other amplifiers.

[0130] Moreover, the disclosed configurations can be adapted to different technologies. For example, disclosed embodiments of amplifiers may be implemented in various manufacturing processes including 3 nm, 5 nm, 7 nm, 10 nm, 16 nm, and 20 nm processes.

[0131] For at least these reasons, the advantages of the disclosed embodiments result in operational amplifiers with improved performance, easier configuration, and/or simpler fabrication.

[0132] It will be understood that not all advantages have been necessarily discussed herein, no particular advantage is required for all embodiments or examples, and other embodiments or examples may offer different advantages.

[0133] According to one aspect of the present disclosure, an amplifier circuit includes a positive biasing circuit coupled to a power node and having a drive PMOS, the drive PMOS for biasing in a subthreshold region. The circuit also includes a negative biasing circuit coupled to a ground node and having a drive NMOS, the drive NMOS for biasing in the subthreshold region. The circuit also includes an amplification circuit coupled to the positive biasing circuit and the negative biasing circuit. The amplification circuit includes a first stage with PMOS transistors and a first boosting stage, one of the PMOS transistors being coupled with the drive PMOS. The amplification circuit also includes a second stage including NMOS transistors and a second boosting stage, one of the matching NMOS transistors being coupled with the drive NMOS. The amplification circuit also includes a resistive element coupled between the first stage and the second stage and an output node connected to the first stage and the second stage.

[0134] According to another aspect of the present disclosure, a folded cascode operational amplifier includes a positive biasing circuit coupled to a power node and including a drive PMOS. The folded cascode also includes a negative biasing circuit coupled to a ground node and including a drive NMOS and a differential input circuit coupled to the positive biasing circuit and the negative biasing circuit. The folded cascode also includes an amplification circuit coupled to the positive biasing circuit and the negative biasing circuit. The amplification circuit has a first stage coupled with the drive PMOS, a second stage coupled with the drive NMOS, and a resistive element coupled between the first stage and the second stage, the resistive element being directly connected to gates of the drive PMOS and the drive NMOS. In the folded cascode, the value of the resistive element is selected to place at least one of the drive PMOS or the drive NMOS in a subthreshold region.

[0135] In accordance with yet another aspect of the present disclosure, an integrated circuit includes a positive biasing area having a drive PMOS for operating in a subthreshold region and a negative biasing area having a drive NMOS for operating in the subthreshold region. The integrated circuit also includes an input area disposed between and respectively neighboring the positive biasing area and the negative biasing; a first boosting area neighboring the input area and the positive biasing area, the first boosting area including PMOS transistors; and a second boosting area neighboring the input area and the negative biasing area, the second boosting area including NMOS transistors. The integrated circuit also includes a resistive area neighboring the first boosting area and the second boosting area, the resistive area including a resistive element directly connected to the drive PMOS and the drive NMOS.

[0136] The foregoing outlines features of several embodiments so that those skilled in the art may better understand the aspects of the present disclosure. Those skilled in the art should appreciate that they may readily use the present disclosure as a basis for designing or modifying other processes and structures for carrying out the same purposes and/or achieving the same advantages of the embodiments introduced herein. Those skilled in the art should also realize that such equivalent constructions do not depart from the spirit and scope of the present disclosure, and that they may make various changes, substitutions, and alterations herein without departing from the spirit and scope of the present disclosure.

[0137] Moreover, while illustrative embodiments have been described herein, the scope thereof includes any and all embodiments having equivalent elements, modifications, omissions, combinations (e.g., of aspects across various embodiments), adaptations and/or alterations as would be appreciated by those in the art based on the present disclosure. For example, the number and orientation of components shown in the exemplary systems may be modified. Further, with respect to the exemplary methods illustrated in the attached drawings, the order and sequence of steps may be modified, and steps may be added or deleted.

[0138] Thus, the foregoing description has been presented for purposes of illustration only. It is not exhaustive and is not limiting to the precise forms or embodiments disclosed. Modifications and adaptations will be apparent to those skilled in the art from consideration of the specification and practice of the disclosed embodiments.

[0139] The claims are to be interpreted broadly based on the language employed in the claims and not limited to examples described in the present specification, which examples are to be construed as non-exclusive. Further, the steps of the disclosed methods may be modified in any manner, including by reordering steps and/or inserting or deleting steps.

## Claims

1. A circuit, comprising: a first circuit comprising a first drive transistor for biasing in a subthreshold region; a second circuit comprising a second drive transistor for biasing in the subthreshold region; a first boosting stage coupled to the first drive transistor and comprising first matching transistors; a second boosting stage coupled to the second drive transistor and comprising second matching transistors; and one or more resistive elements connecting the first boosting stage and the second boosting stage.
2. The circuit of claim 1, wherein the first matching transistors or the second matching transistors comprise a pair of PMOS transistors.
3. The circuit of claim 2, wherein the pair of PMOS transistors have the same dimensions.
4. The circuit of claim 3, wherein gates of the pair of PMOS transistors are connected to a first input substage.
5. The circuit of claim 1, wherein the first matching transistors or the second matching transistors comprise a pair of NMOS transistors.
6. The circuit of claim 5, wherein the pair of NMOS transistors have the same dimensions.
7. The circuit of claim 1, wherein the first drive transistor is a PMOS transistor and the second drive transistor is an NMOS transistor.
8. The circuit of claim 1, wherein the first circuit comprises at least two PMOS transistors connected in parallel to a power node.
9. The circuit of claim 8, wherein the second circuit comprises at least two NMOS transistors connected in parallel to a ground node.
10. The circuit of claim 1, wherein the one or more resistive elements comprise at least one of a MOS transistor or a resistor.
11. A method, comprising: configuring a first transistor connected to a first drive transistor and a second transistor connected to a second drive transistor of an amplifier circuit for operation in a

saturation region; configuring the first drive transistor and the second drive transistor for operation in a subthreshold region; powering the amplifier circuit; and inputting a signal at a differential input of the amplifier circuit.

**12.** The method of claim 11, wherein the input signal is a clock signal.

**13.** The method of claim 12, further comprising: using an amplified signal generated by the amplifier circuit as a control signal in a duty cycle corrector.

**14.** The method of claim 11, wherein at least one or more resistive elements couple the first transistor and the second transistor.

**15.** The method of claim 14, wherein the one or more resistive elements comprise a MOS resistor.

**16.** The method claim 11, further comprising: adjusting drop voltages in the first drive transistor and the second drive transistor to reduce a supply voltage.

**17.** The method of claim 11, wherein configuring the first transistor and the second transistor comprises configuring the first drive transistor in a p-type wide-swing cascade current mirror.

**18.** The method of claim 17, wherein configuring the first transistor and the second transistor comprises configuring the second drive transistor in an n-type wide-swing cascade current mirror.

**19.** A duty cycle corrector, comprising: a first circuit connected to an input for a clock signal; a second circuit comprising a first drive transistor and connected to a power node of the duty cycle corrector; a third circuit comprising a second drive transistor and connected to a ground node of the duty cycle corrector; and at least two boosting stages respectively coupled to the first drive transistor and the second drive transistor and one or more resistive elements connecting the at least two boosting stages, wherein: the at least two boosting stages respectively comprise a pair of PMOS transistors having the same dimensions and a pair of NMOS transistors having the same dimensions; and the one or more resistive elements are selected to set a gate voltage of the first drive transistor and the second drive transistor for operation in a subthreshold region.

**20.** The duty cycle corrector of claim 19, wherein the one or more resistive elements comprise at least one of a resistor, a capacitor, or an inductor.

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